EV02 151597

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No
Priority Filing Date February 19, 1998
Inventor
Assignee Micron Technology, Inc. and Applied Materials, Inc.
Priority Group Art Unit
Priority Examiner P. Hassanzadeh Ph.D.
Attorney's Docket No
Title: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and Methods
of Effecting Plasma Enhanced Chemical Vapor Deposition

INFORMATION DISCLOSURE STATEMENT

References - - See attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, copending application of the above-identified application. The above-identified application is a divisional application of co-pending application Serial No. 09/026,042, filed February 19, 1998, upon which the above-identified application relies for a priority date under 35 U.S.C. §120. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. §1.98(d) and MPEP §609(2). As a courtesy, Applicant submits copies of the cited foreign references and articles for review.

Citation of these references is respectfully requested.

Respectfully submitted,

Date: 3211-14,2002

Frederick M. Fliegel, Ph.D.

Reg. No. 36,138

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*EXAMINER Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line intrough citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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